

S/N UnknownPATENTIN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Stephen Y. Chou
Serial No.: Unknown
Filed: Herewith
Title: IMPROVED RELEASE SURFACES, PARTICULARLY FOR USE IN NANOIMPRINT LITHOGRAPHY

Examiner: Unknown
Group Art Unit: Unknown
Docket: 600.426US2

INFORMATION DISCLOSURE STATEMENT

Box Patent Application
Commissioner for Patents
Washington, D.C. 20231

In compliance with the duty imposed by 37 C.F.R. § 1.56, and in accordance with 37 C.F.R. §§ 1.97 *et. seq.*, the enclosed materials are brought to the attention of the Examiner for review in connection with the above-identified patent application. Pursuant to the provisions of MPEP 609, Applicant requests that a copy of the 1449 form, initialed as being considered by the Examiner be returned to the Applicant.

In accordance with 37 C.F.R. §1.98(d), copies of the listed documents are not provided as these references were previously cited by or submitted to the U.S. Patent Office in connection with Applicant's prior U.S. application, Serial No. 09/107,006, filed on June 30, 1998, which is relied upon for an earlier filing date under 35 U.S.C. §120.

Applicant respectfully request consideration of these references during prosecution of the above-identified matter. The Examiner is invited to contact the Applicant's Representative at the below-listed telephone number if there are any questions regarding this communication.

Respectfully submitted,

STEPHEN Y. CHOU

By his Representatives,

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.
P.O. Box 2938
Minneapolis, MN 55402
(612) 359-3261

Date 10/28/01

By 

Gary J. Speier
Reg. No. 45,458

"Express Mail" mailing label number: EL873861011US
Date of Deposit: October 29, 2001

Sheet 1 of *P*

Form 1449*	Atty. Docket No.: 600.426US2	Serial No. Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Applicant: Stephen Y. Chou	
	Filing Date: Herewith	Group: Unknown

U.S. PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	3,743,842	07/03/1973	Smith, H.I., et al.	250	320	01/14/72
	4,310,743	01/12/1982	Seliger, R.L.	219	121 EB	09/24/79
	4,325,779	04/20/1982	Rossetti, J.J.	156	651	11/17/80
	4,383,026	05/10/1983	Hall, T.M.	430	325	08/24/81
	4,450,358	05/22/1984	Reynolds, G.O.	250	492.1	09/22/82
	4,498,009	02/05/1985	Reynolds, G.O.	250	452.1	09/22/82
	4,516,253	05/07/1985	Novak, W.T.	378	034	04/25/83
	4,552,615	11/12/1985	Amendola, A., et al.	158	659.1	05/21/84
	4,576,678	03/18/1986	Shibata, H.	156	643	09/13/84
	4,606,788	08/19/1986	Moran, P.L.	156	656	04/03/85
	4,731,155	03/15/1988	Napoli, L.S., et al.	156	643	04/15/87
	4,832,790	05/23/1989	Rossetti, J.J.	156	651	02/24/87
	5,277,749	01/11/1994	Griffith, J.H., et al.	156	643	10/17/91
	5,861,113	01/19/1999	Choquette, S.J., et al.	264	1.24	08/01/96

FOREIGN PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes No
	1196749	01/30/1988	European	G11B	7/26	
	244884	03/28/1986	European	B29C	33/64	
	401196749	08/08/1989	Japan	G11B	7/26	
	4255307	09/10/1992	Japan	B29C	33/38	
	4332694	08/05/1991	European	B41N	1/12	
	9117565	11/14/1991	PCT	H01L	21/00	
	98/26913	06/25/1998	PCT	B29C	33/58	

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

**Examiner Initial	
	Broere, et al., "250-A Linewidths with PMMA Electron Resist", <u>Applied Physics Letter 33 (5)</u> , 1978 American Institute of Physics, 392-394, (September 1, 1978)
	Chou, S.Y., et al., "Imprint Lithography with 25-Nanometer Resolution", <u>Science, Vol 272</u> , 85-87, (April 5, 1996)
	Early, K., et al., "Absence of Resolution Degradation in X-Ray Lithography for Wavelength from 4.5nm to 0.83nm", <u>Microelectronic Engineering 11</u> , Elsevier Science Publishers B.V., 317-321, (1990)
	Fischer, et al., "10 nm Electron Beam Lithography and sub-50 nm Overlay Using a Modified Scanning Electron Microscope", <u>Applied Physics Letter 62 (23)</u> , 1993 American Institute of Physics, 2989-2991, (June 7, 1993)

Examiner

Date Considered

*Substitute Disclosure Statement Form (PTO-1449)

--EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Sheet 2 of *P*

Form 1449*	Atty. Docket No.: 600.426US2	Serial No. Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Applicant: Stephen Y. Chou	
	Filing Date: Herewith	Group: Unknown

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

**Examiner
Initial

	Hara, et al., "An Alignment Technique Using Diffracted Moire Signals", <u>J. Vac. Sci. Technol. B 7 (6)</u> , 1989 American Vacuum Society, 1977-1979, (Nov./Dec. 1989)
	Harmening, et al., "Molding of Threedimensional Microstructures by the Liga Process", <u>Proceedings IEEE : Micro Electro Mechanical Systems</u> , Travemunde, Germany, 202-207, (1992)
	Li, et al., "Molding of Plastic Components Using Micro-EDM Tools", <u>IEEE/CHMT International Electronics Manufacturing Technology Symposium</u> , 145-149, (1992)
	Nomura, et al., "Moire Alignment Technique for the Mix and Match Lithographic System", <u>J. Vacuum Society Technol. B 6 (1)</u> , American Vacuum Society, 394-398, (Jan/Feb 1988)

Examiner

Date Considered

*Substitute Disclosure Statement Form (PTO-1449)

**EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 2001. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.